## IN THE CLAIMS:

Please AMEND the claims as follows:

1. (CURRENTLY AMENDED) A gas discharge panel substrate assembly comprising:

electrodes formed on a substrate,

a dielectric layer covering the electrodes, and

a protective layer covering the dielectric layer and in contact with a discharge space, wherein

the protective layer includes MgO and at least one compound selected from the group consisting of an Al compound, a Y compound, a Zn compound, a Zr compound, a Ta compound and SiC, and has having an ultraviolet shielding function, and

the dielectric layer is a CVD filmSiO<sub>2</sub> film of a thickness in the range of 5 to 15 µm.

- 2. (CURRENTLY AMENDED) A gas discharge panel substrate assembly of claim 1, wherein the protective layer comprises a layer which shields the dielectric layer of the SiO<sub>2</sub> film from light having a wavelength of 200 nm or less generated by a discharge in the discharge space.
- 3. (PREVIOUSLY PRESENTED) A gas discharge panel substrate assembly of claim 1, wherein said at least one compound is a compound having a bandgap of 6.2 eV.
- 4. (CURRENTLY AMENDED) A gas discharge panel substrate assembly of claim 1, wherein the dielectric layer contains a CVD-SiO<sub>2</sub>hydrocarbon bond therein.
- 5. (CURRENTLY AMENDED) A gas discharge panel substrate assembly comprising:

electrodes formed on a substrate,

a dielectric layer formed on the substrate so as to cover the electrodes and made of a CVD filmSiO<sub>2</sub> film having thickness in the range of 5 to 15 µm,

an ultraviolet shielding layer formed on the dielectric layer and made of a compound having an ultraviolet shielding function to shield the dielectric layer from ultraviolet light generated by a discharge in a discharge space of the assembly, the compound being selected from the group consisting of an Al compound, a Y compound, a Zn compound, a Zn compound, a

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Ta compound and SiC, and

a protective layer formed on the ultraviolet shielding layer and made of MgO.

- 6. (CANCELED)
- 7. (CURRENTLY AMENDED) A gas discharge panel substrate assembly of claim 5, wherein the ultraviolet shielding layer shields the dielectric layer from ultraviolet light having a wavelength of 200 nm or less.
- 8. (CURRENTLY AMENDED) A gas discharge panel substrate assembly of claim 5, wherein the dielectric layer contains a CVD-SiO<sub>2</sub>hydrocarbon bond therein.
  - 9. (CANCELED)
  - 10. (CANCELED)
  - 11. (CANCELED)
  - 12. (CANCELED)
  - 13. (CANCELED)
- 14. (CURRENTLY AMENDED) An AC type gas discharge panel using the gas discharge panel substrate assembly as disclosed in claim 1 as a gas discharge panel substrate assembly in the front sidecomprising:
  - a front substrate having display electrodes;
- a dielectric layer covering the display electrodes, the dielectric layer having a thickness in the range of 5 to 15 µm, and being a SiO<sub>2</sub> film having a hydrocarbon bond therein;
  - a back substrate having a phosphor;
- a discharge space between the front substrate and the back substrate and having a discharge gas sealed therein; and

an ultraviolet shielding layer formed on the SiO<sub>2</sub> film and containing a compound which shields the SiO<sub>2</sub> film from ultraviolet light generated by a discharge in the discharge space and is selected from the group consisting of an Al compound, a Y compound, a Zn compound, a Zr compound, a Ta compound and SiC.

15. (CURRENTLY AMENDED) An AC type gas discharge panel using the gas discharge panel substrate assembly as disclosed in claim 5 as a gas discharge panel substrate

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assembly in the front side comprising:

a front substrate having display electrodes;

a dielectric layer covering the display electrodes, having a thickness in the range of 5 to 15 µm, and being a SiO<sub>2</sub> film having a hydrocarbon bond therein;

a back substrate having a phosphor;

a discharge space between the front substrate and the back substrate and having a discharge gas sealed therein;

a protective layer covering a surface of the dielectric layer facing the discharge space and made of MgO; and

an ultraviolet shielding layer formed between the SiO<sub>2</sub> film and the protective layer, wherein the ultraviolet shielding layer shields the dielectric layer from ultraviolet light generated by a discharge in the discharge space and contains a compound selected from the group consisting of an Al compound, a Y compound, a Zn compound, a Zr compound, a Ta compound and SiC.

16. (CURRENTLY AMENDED) A gas discharge panel substrate assembly comprising:

electrodes formed on a glass substrate;

a dielectric layer made of a sheet frit glass formed on the substrate by baking and containing a hydrocarbon bond therein;

an intermediate layer formed on the dielectric layer and shielding the dielectric layer from vacuum ultraviolet light from generated by a discharge in a discharge space of the assembly, the intermediate layer being made of at least one compound selected from the group consisting of an Al compound, a Y compound, a Zn compound, a Zr compound, a Ta compound and SiC; and a protective layer covering the intermediate layer and made of MgO.

## 17. (CANCELED)

18. (PREVIOUSLY PRESENTED) A gas discharge panel substrate assembly of claim 16, wherein the intermediate layer is a ZrO<sub>2</sub> layer.